

Semi-conductor Detectors

HEP and Accelerators

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Outline

- Semiconductor Detectors
 - A Brief Overview
 - Radiation Damage
- Silicon Strip Detectors
- Pixel Detectors
 - Hybrid Pixel Detectors
 - Integrated Devices
 - MAPS
 - DEPFET
 - HV-CMOS and HR-CMOS
 - 3D geometry
- Diamond Detectors
- LHC
- SuperKEKB
- Outlook

Basics

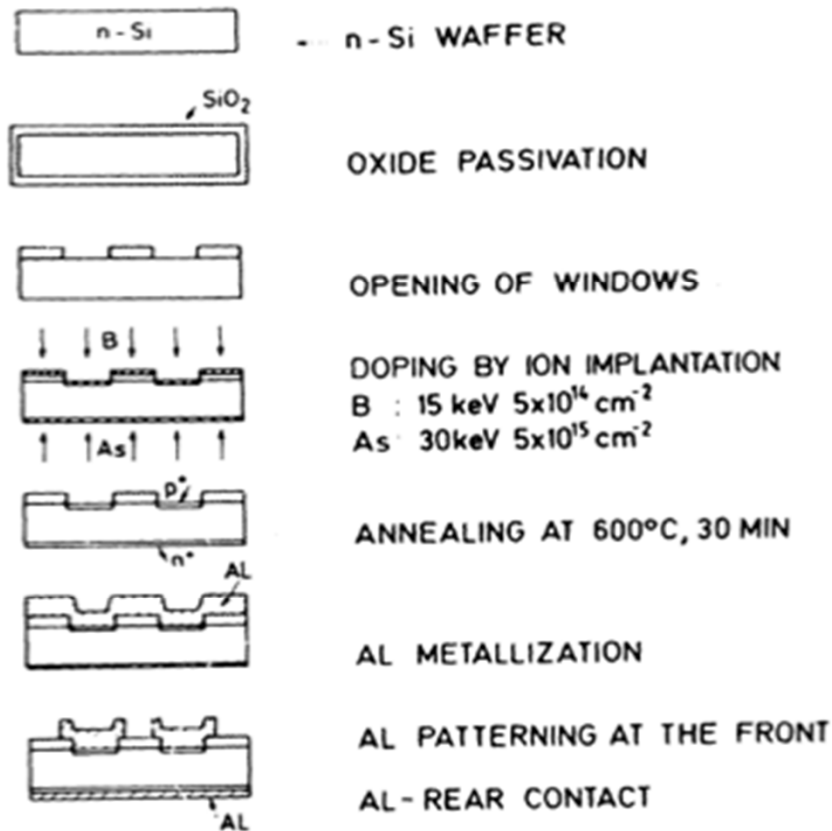


Fig. 2. The planar process for detector fabrication.

Kemmer Process (eg. NIM 226 (1984) 89-93)

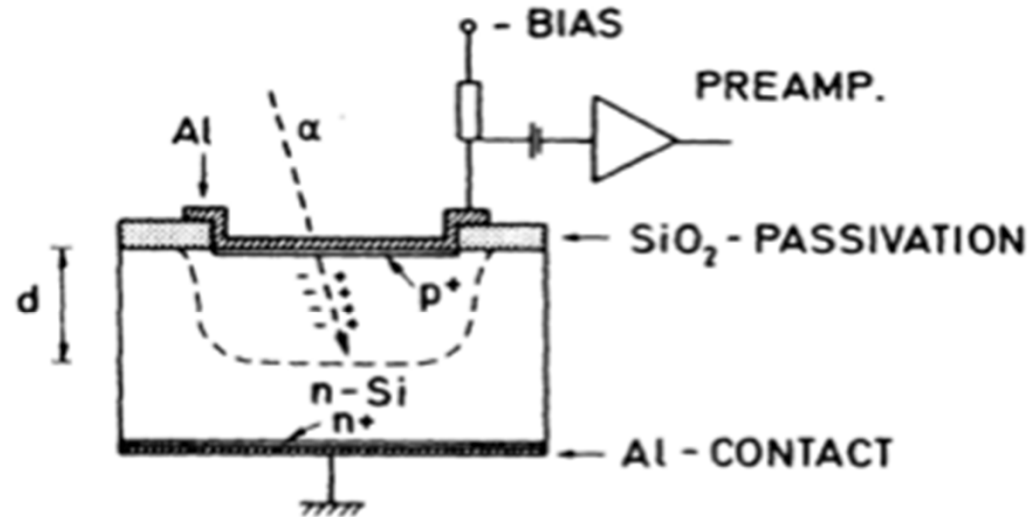


Fig. 1. The $p^+ n$ junction detector.

Basic Semiconductor materials:

Silicon

Ge

GaAs

CdTe

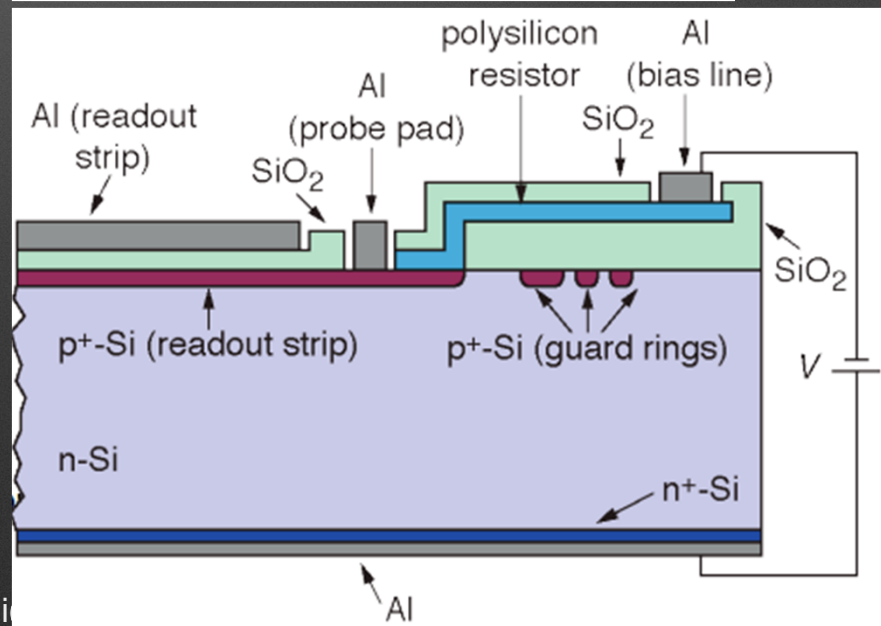
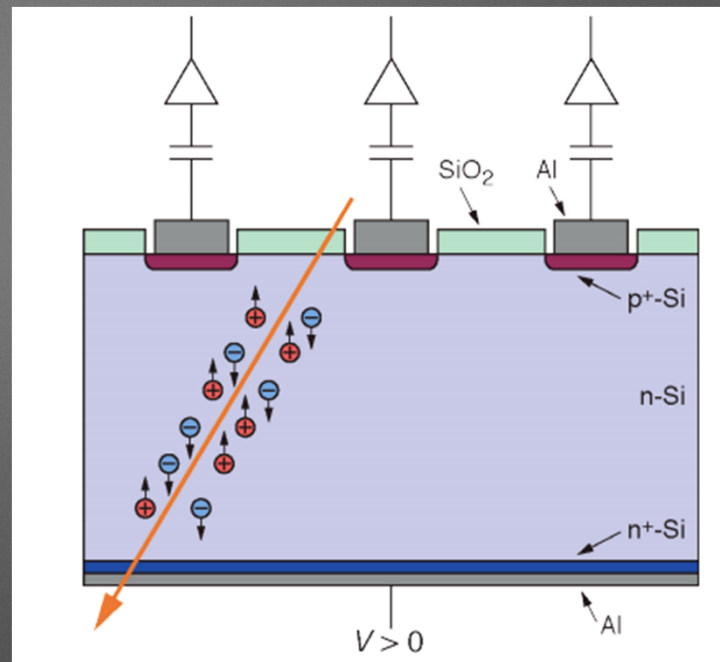
CdZnTe

Diamond

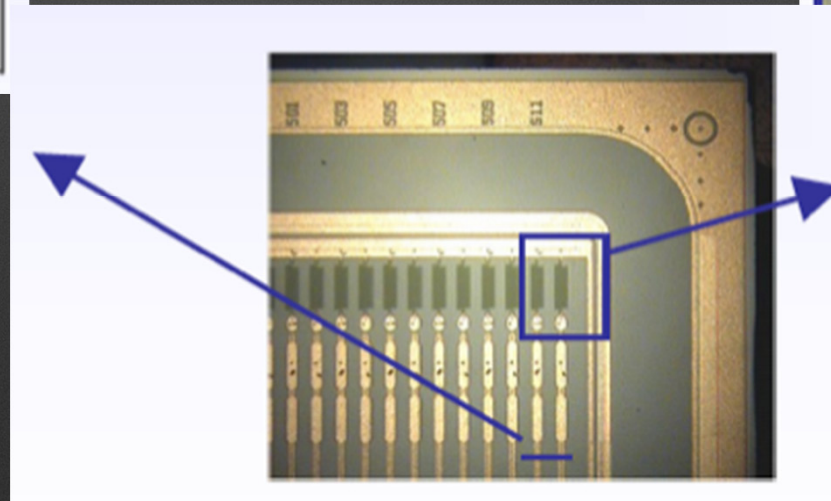
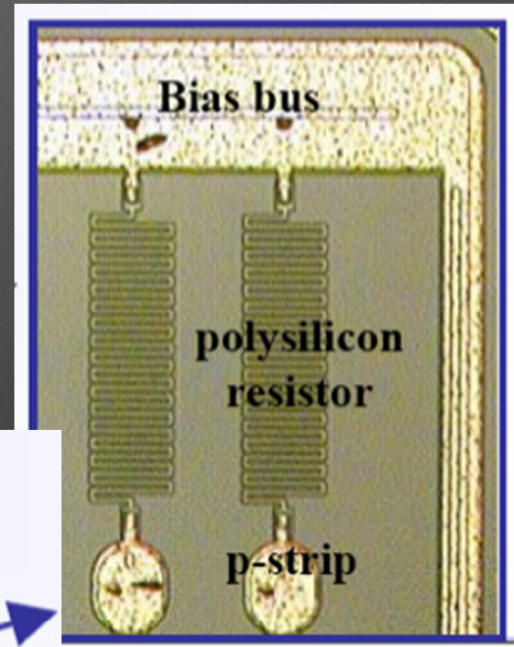
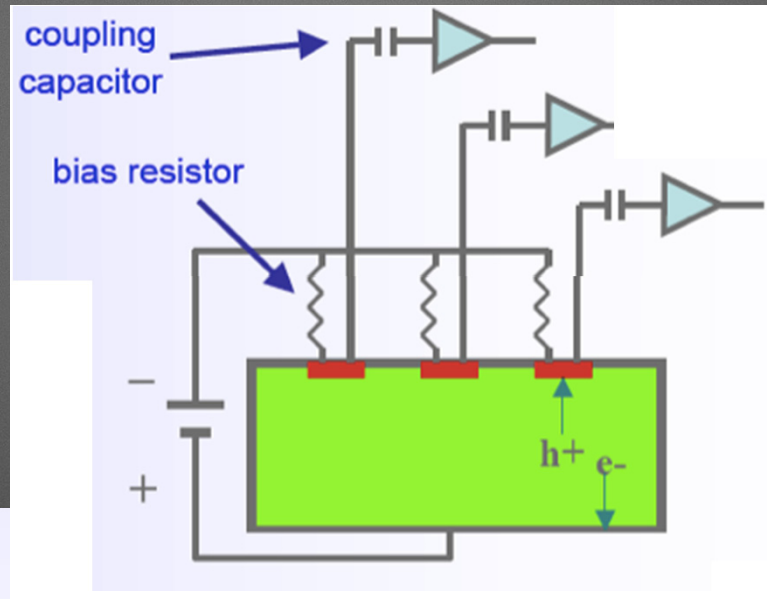
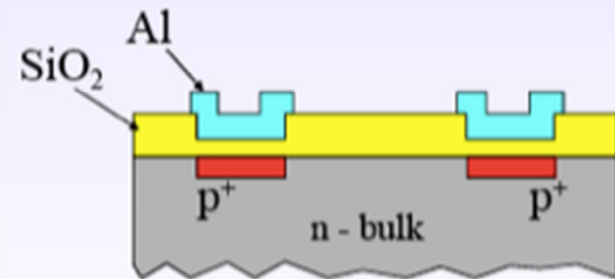
Silicon Carbide, ...

Semiconductor Detectors

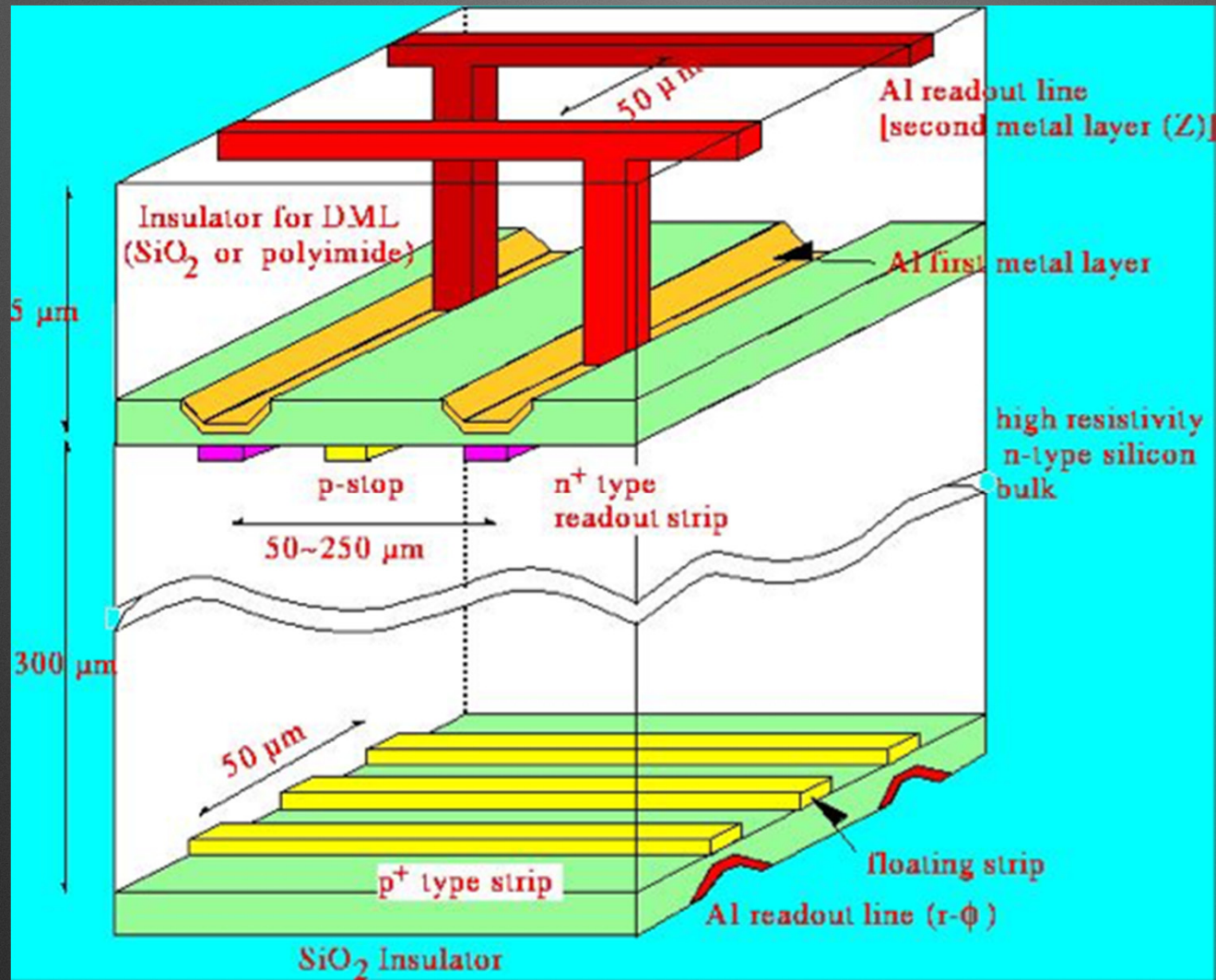
- Semiconductor Diode detectors have been used, and highly evolved for decades.
- Technology highly developed but high specialised.



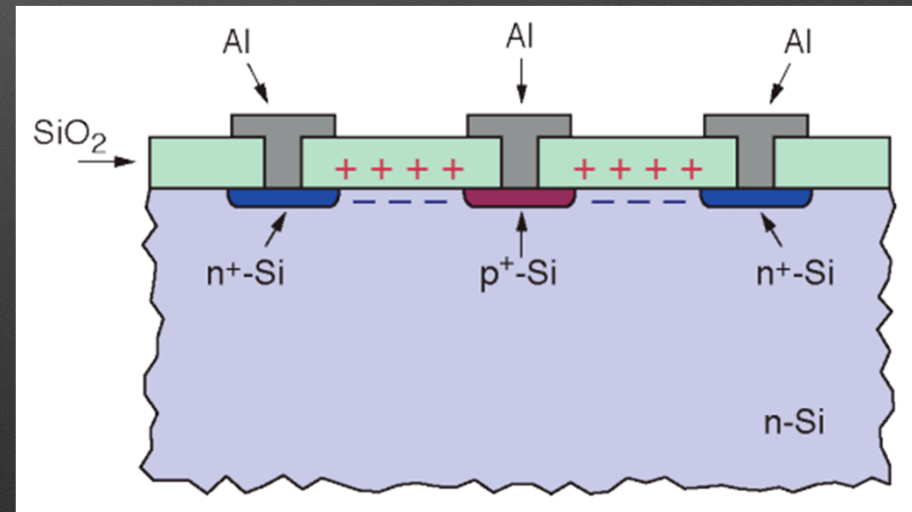
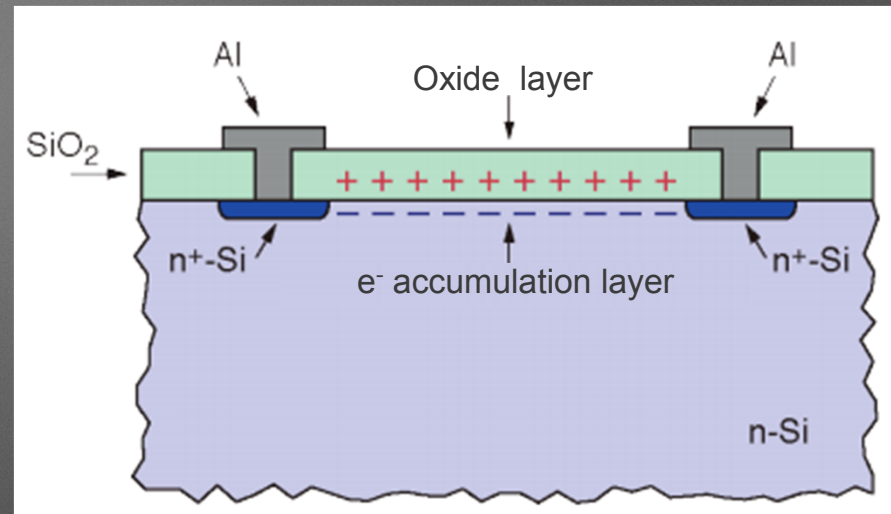
Sophisticated integration ...



Double-sided Silicon Detectors



- n-side (back-side)
 - positive (fixed) charge at SiO_2 - Si interface attracts electrons to n-side.
 - Electron accumulation shorts n-side electrodes
 - p^+ “isolation” required



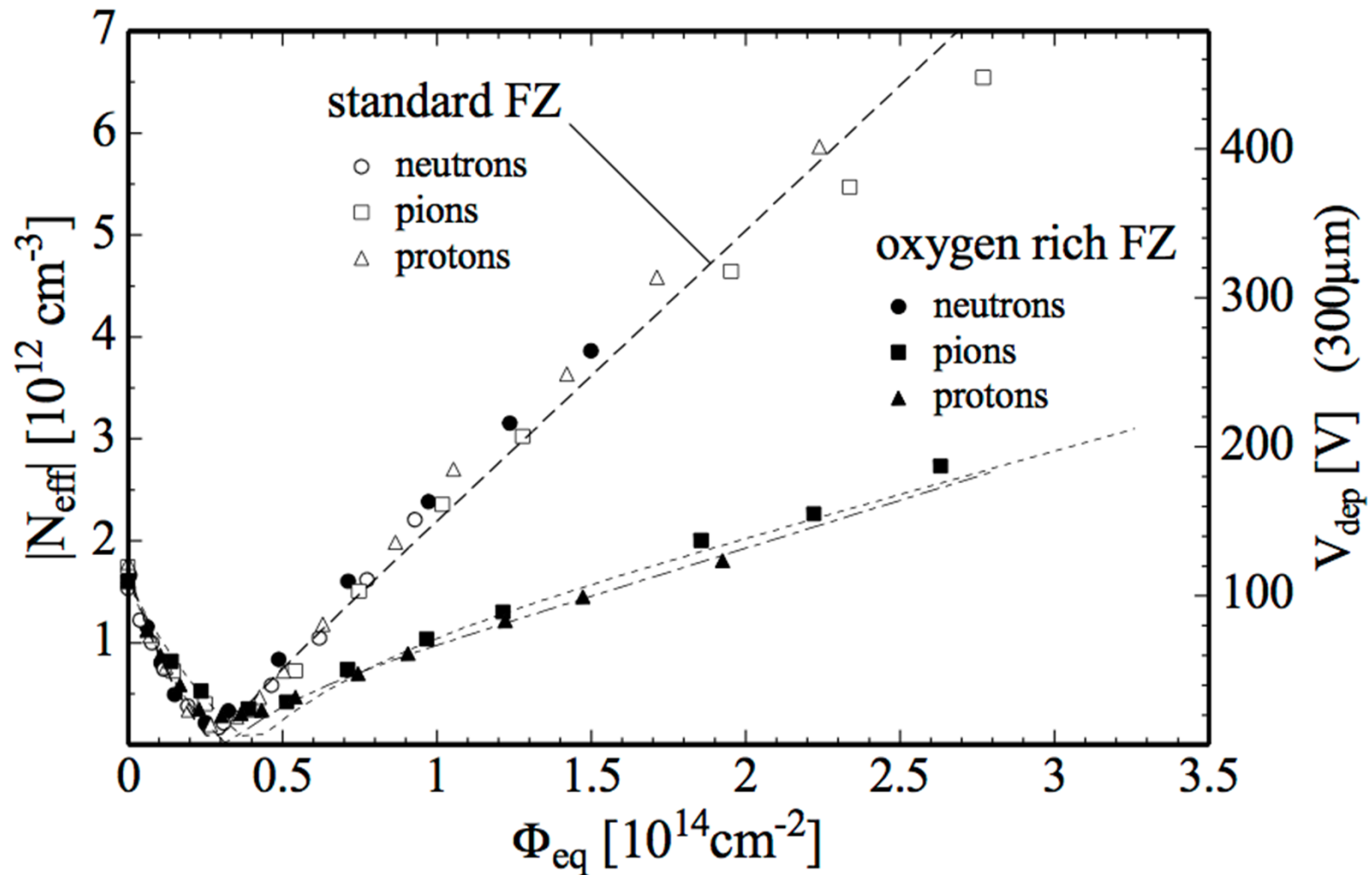
Radiation Damage

Three main macroscopic effects are seen in high-resistivity diodes following energetic hadron irradiation:

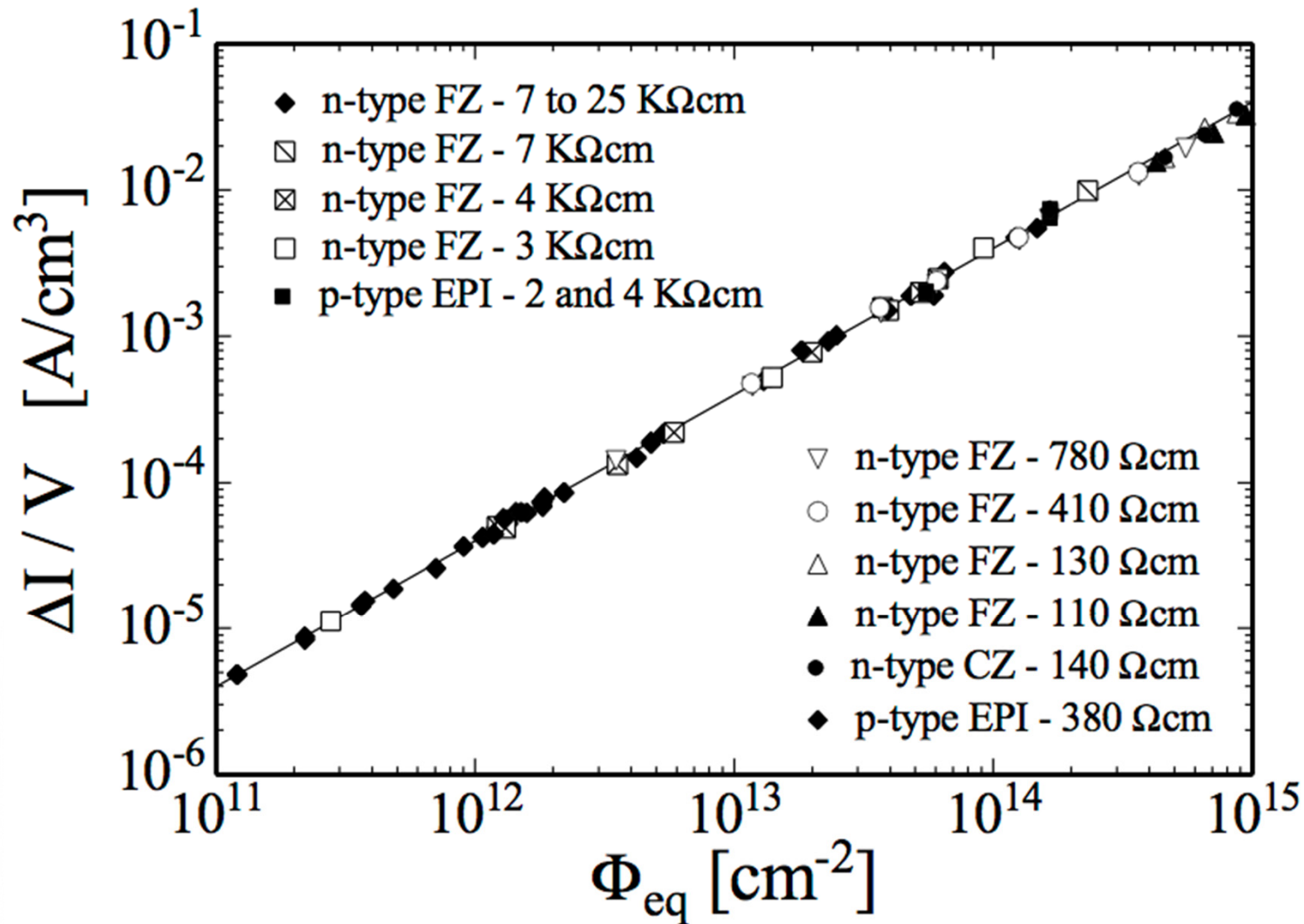
- Change of the doping concentration with severe consequences for the operating voltage needed for total depletion.
- Fluence proportional increase in the leakage current, caused by creation of recombination/generation centres
- Deterioration of charge collection efficiency due to charge carrier trapping leading eventually to a reduction in the signal height produced by mip's.

$$V_{\text{dep}} = \frac{q_0}{2\epsilon\epsilon_0} |N_{\text{eff}}| d^2$$

- Defect Engineering
- Thin detectors
- High Bias Operation



$$I = \alpha \cdot \Phi_{eq} \cdot V$$

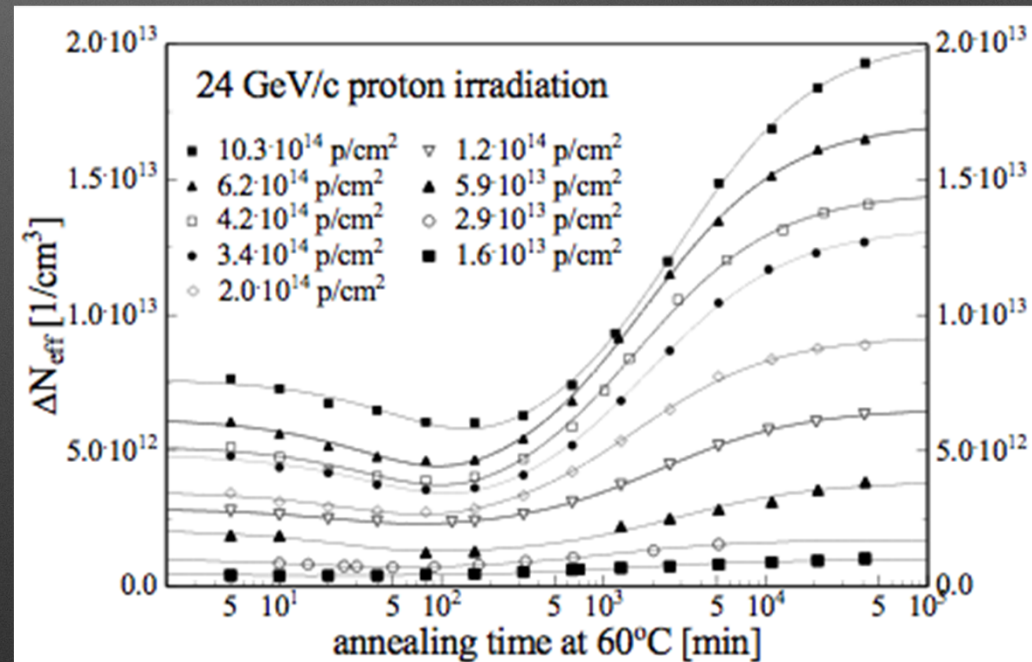


Effect of Temperature

- Strong current reduction with reduced temperature.
- (also Current Annealing)

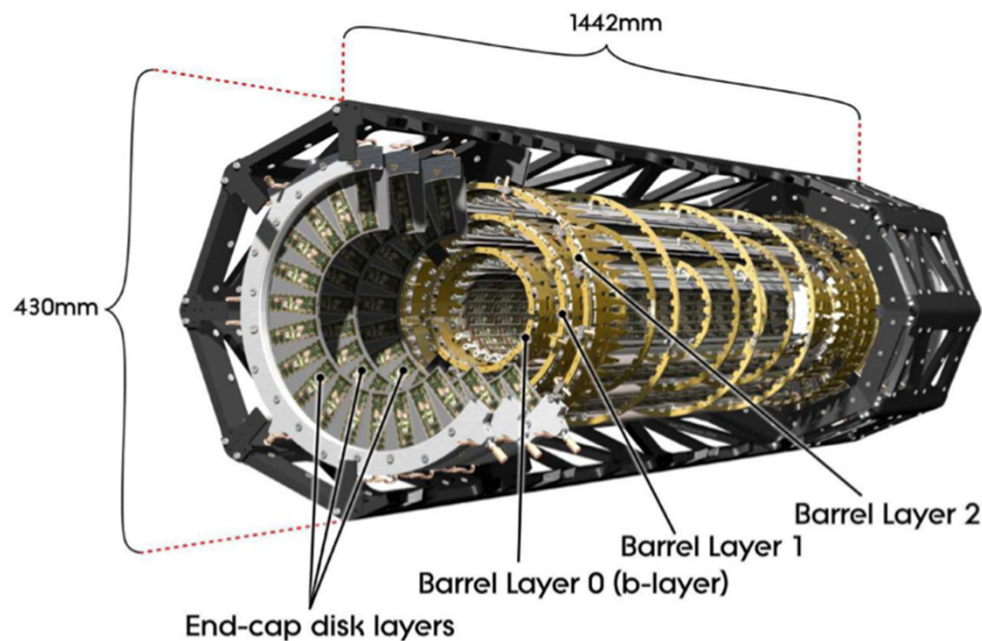
$$I(T) \propto T^2 \exp\left(-\frac{E_g}{2k_B T}\right)$$

- Reverse Annealing of Effective Carrier concentration

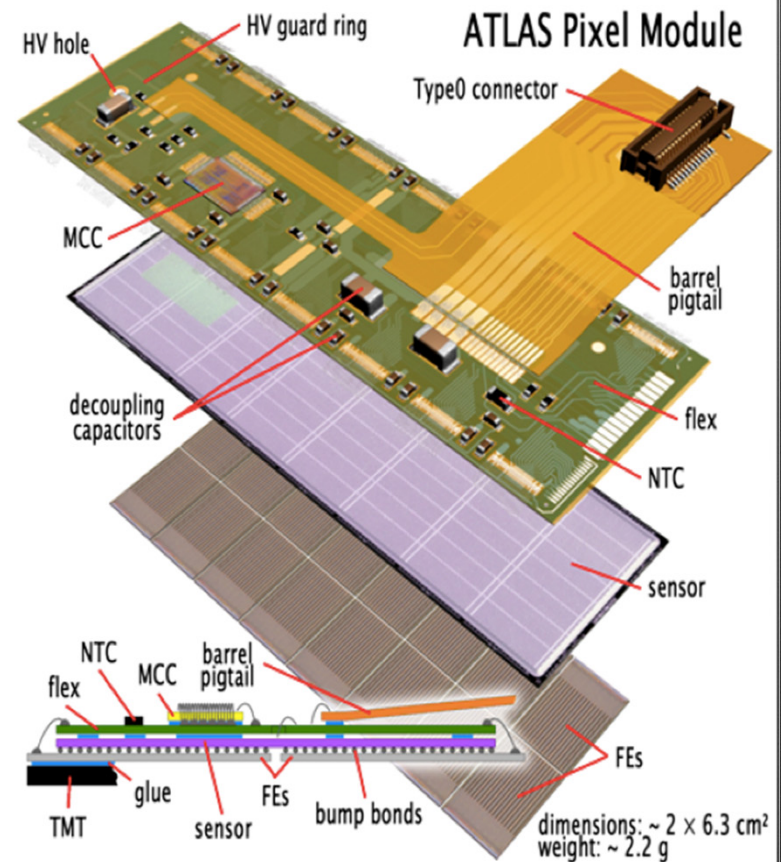


Hybrid Pixel Detectors

- Electronics chip and sensor chip independently produced, bump bonded



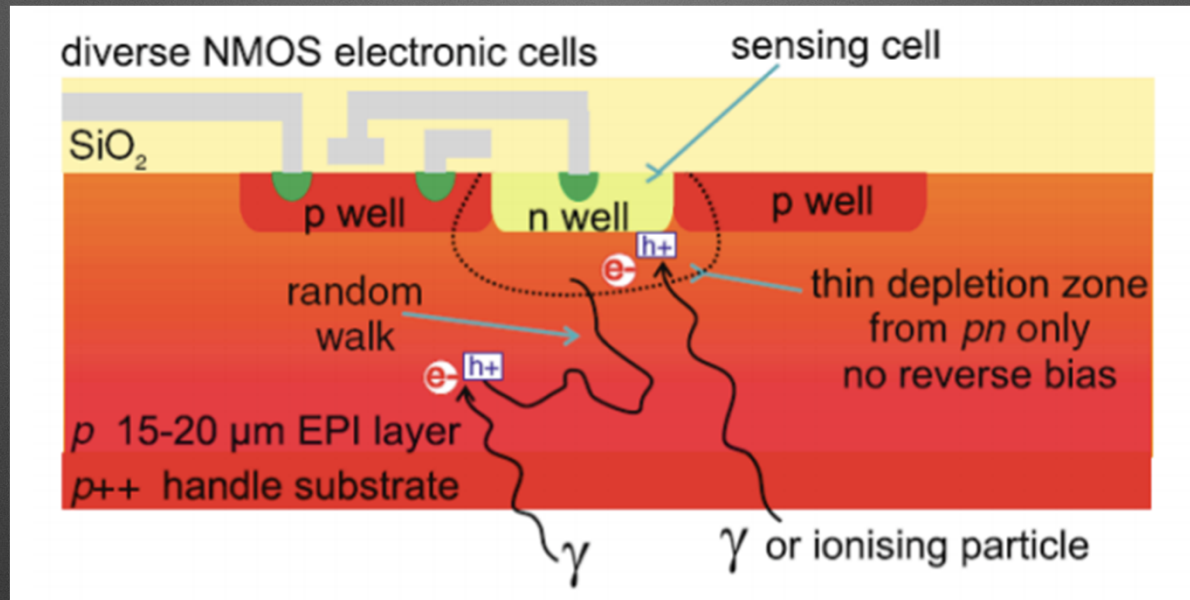
(a)



(b)

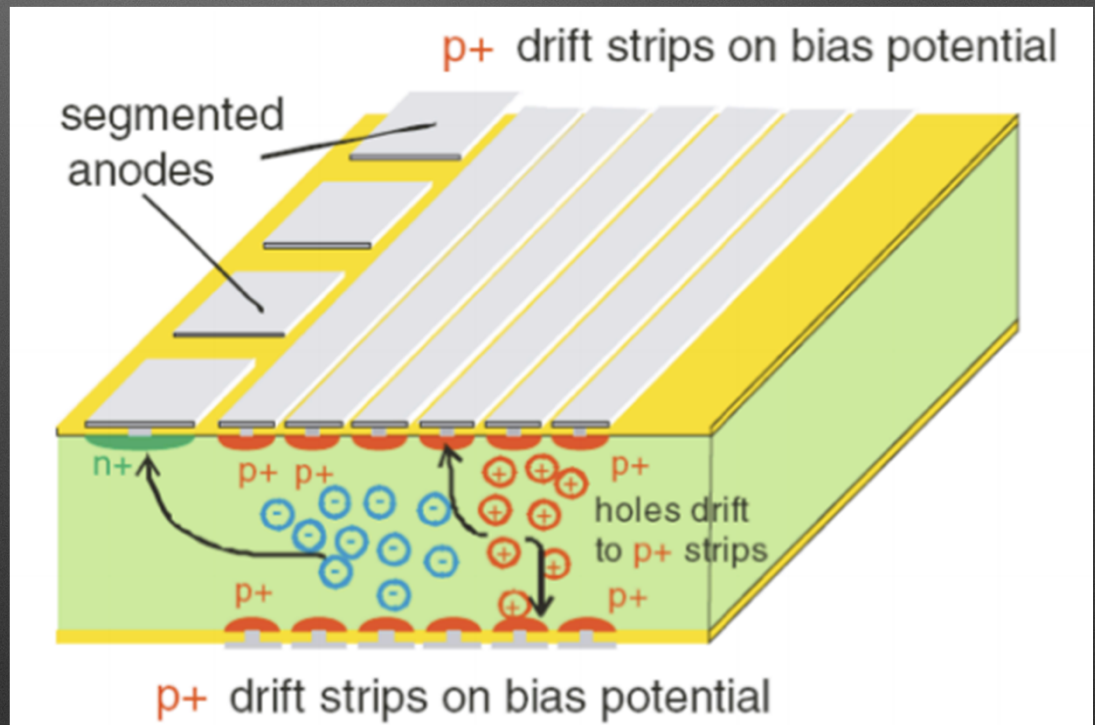
Integrated Pixel Detectors - MAPS

- Electronics and detector element on a single substrate



Silicon Drift Detectors

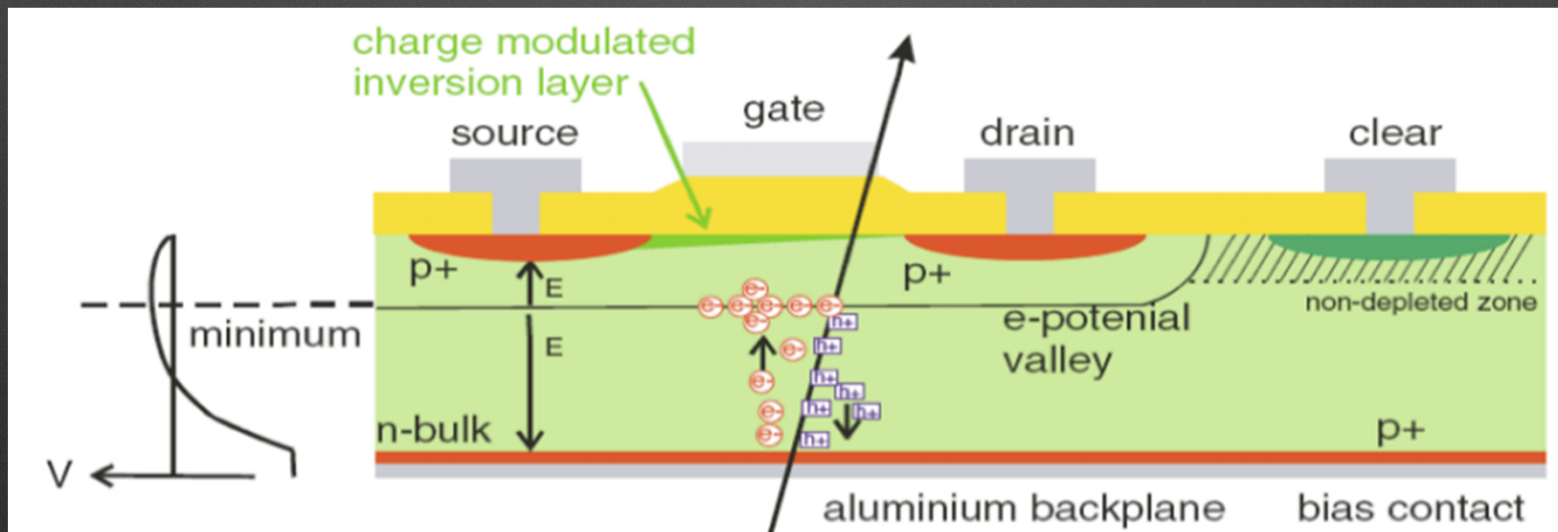
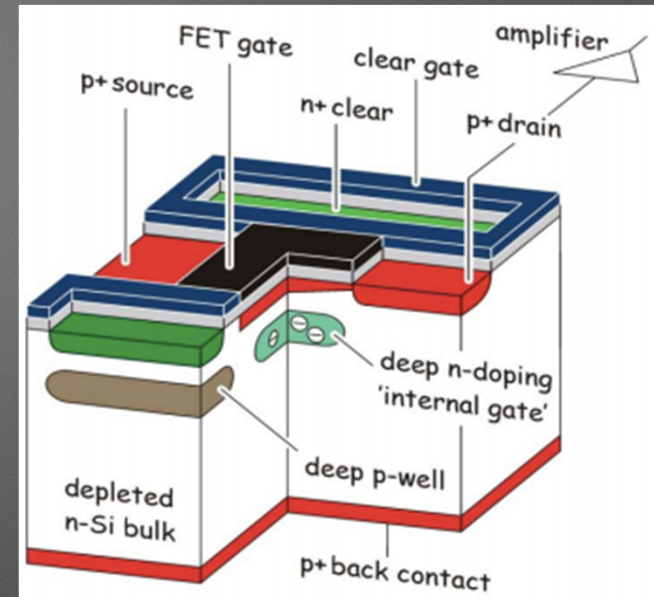
- Positive Electrodes set up Drift Potential
- Electrons drifted to readout anode pads.
- Time/position \rightarrow 2D position.



F. Hartmann, Springer, 2009

Integrated Pixel Detectors - DEPFET

- Belle II Pixel detector



Thinning of silicon detectors

- eg. Belle II PXD
- Rather complicated process.
- Major benefits

a) oxidation and back side implant of top wafer



Handle <100> Wafer

Custom made SOI Wafer

b) wafer bonding and grinding/polishing of top wafer

c) process → passivation



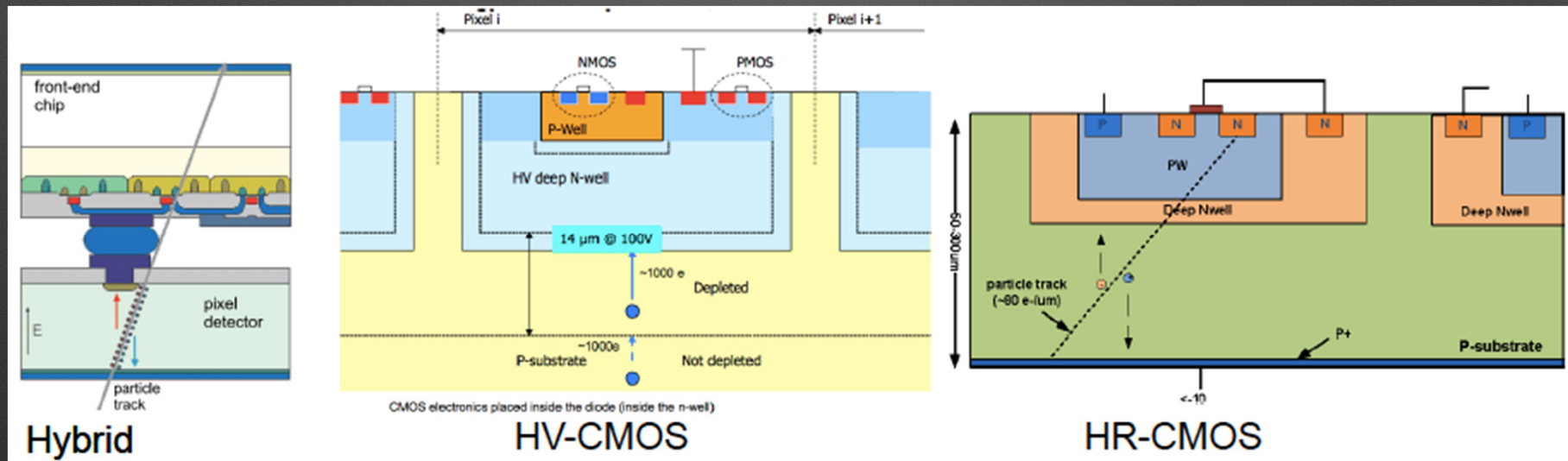
open backside passivation



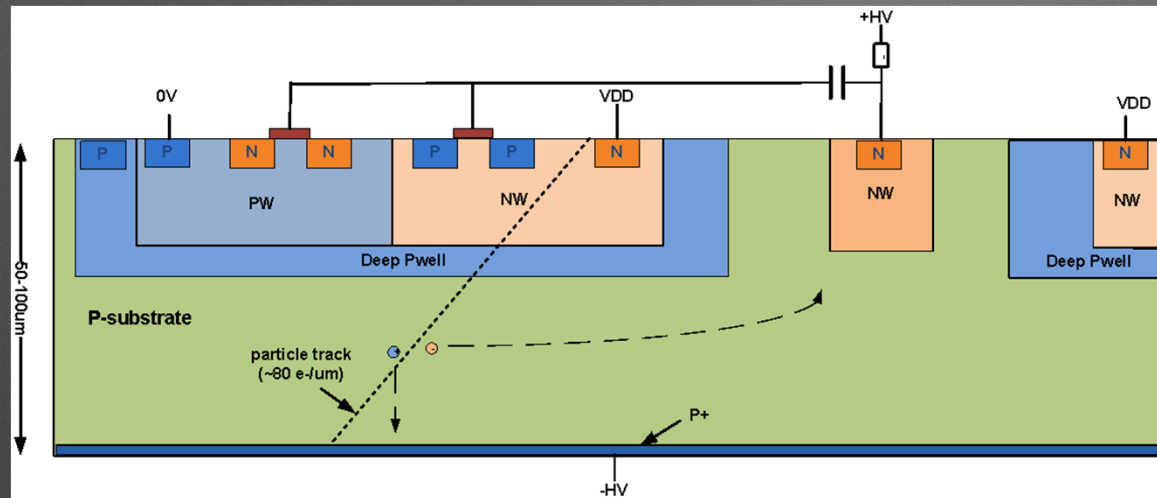
d) anisotropic deep etching opens "windows" in handle wafer

Integrated Pixel Detectors: HV-CMOS and HR-CMOS

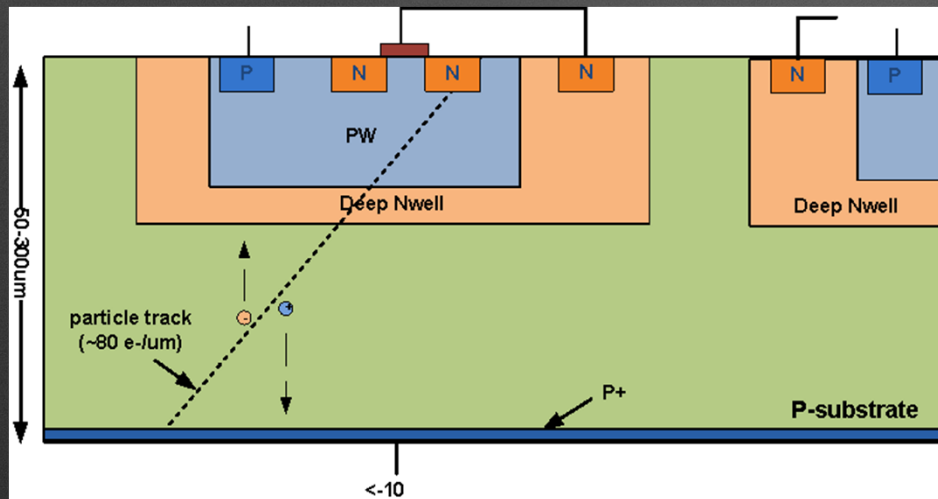
- With a High Resistivity Substrate, the depletion region can be increased over that of the MAPS detectors.
- CMOS processing widely available, adaptable to HV and HR modification



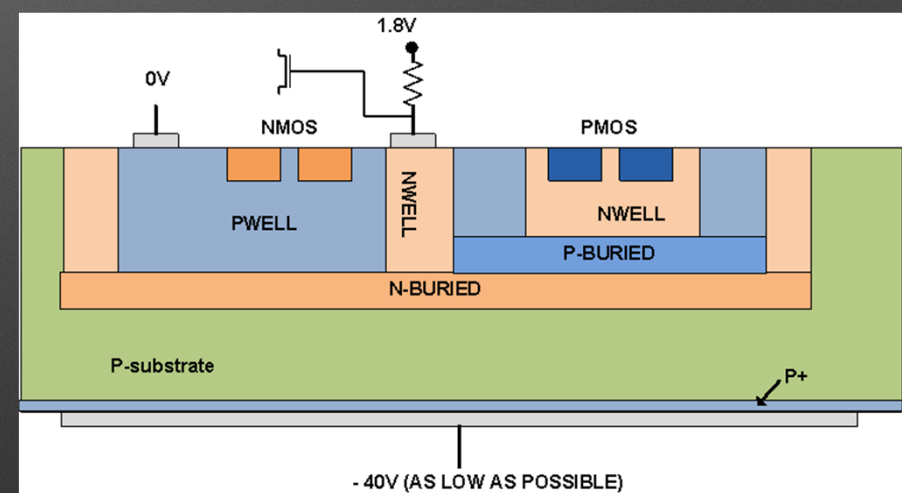
HR-CMOS Options



Drift structure



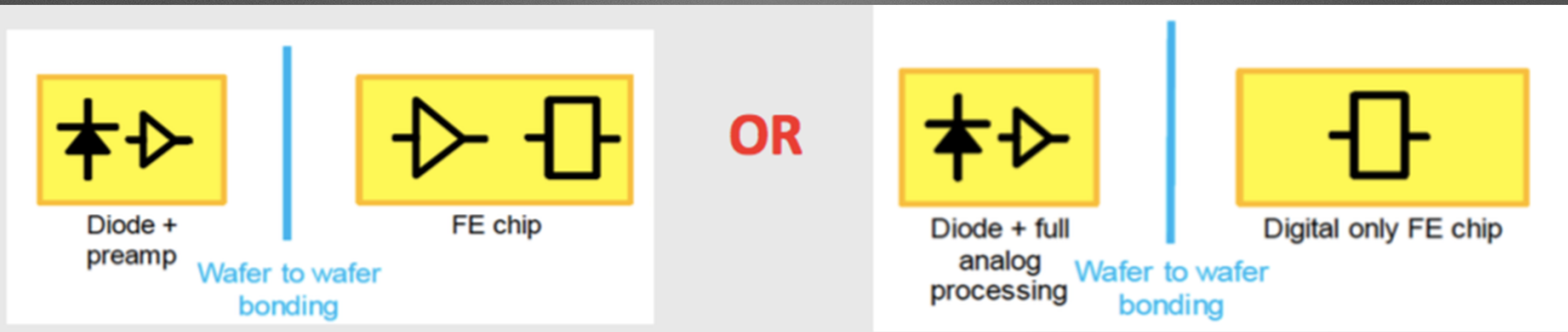
Simple well structure



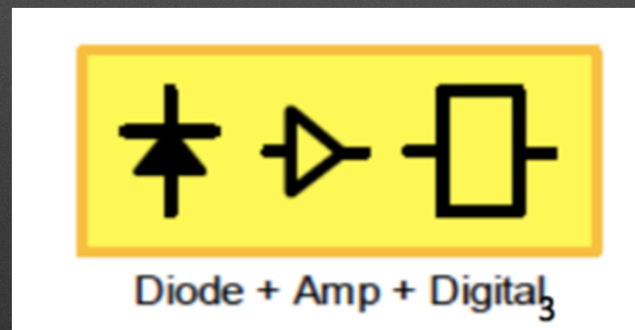
Triple Well Structure

Integration Possibilities, HV-CMOS/HV-CMOS Hybrid Pixel Development

- Amplifier / Discriminator (~100 transistors) per Pixel, Bonded to Digital R/O Chip (>100M transistors)

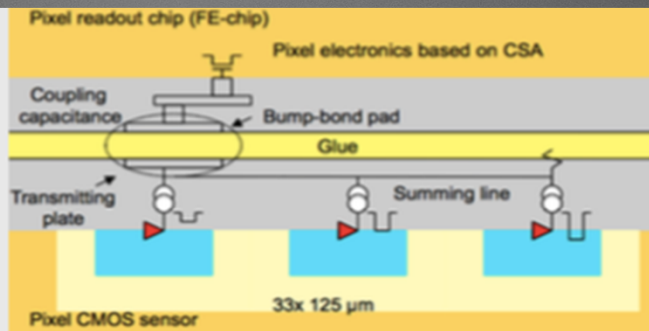


- Long-term aim: full integration on single, depleted substrate:



glue bonding

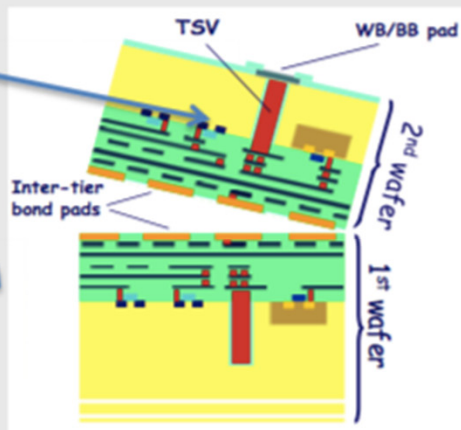
capacitive
coupling
using glue
bonding



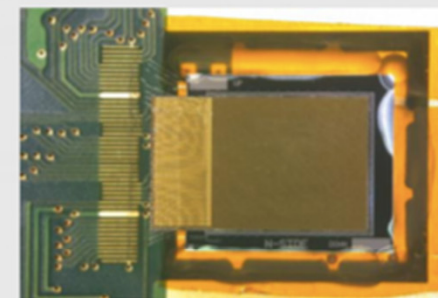
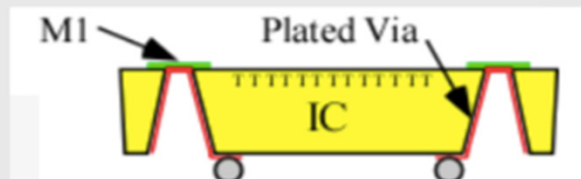
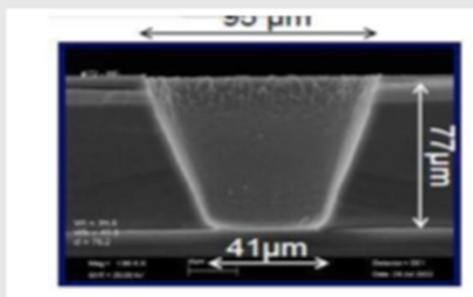
FE-I4

HV-CMOS
(I. Peric et al)

TSVs



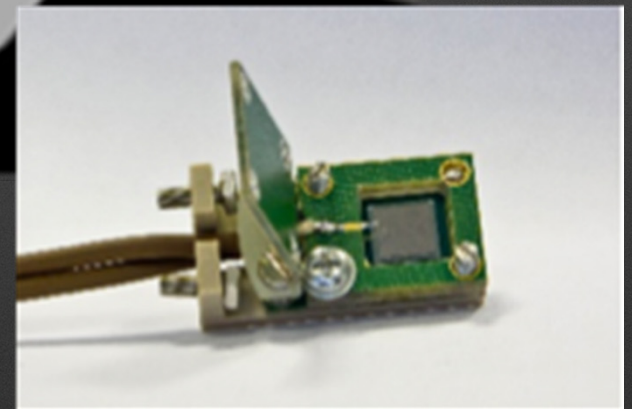
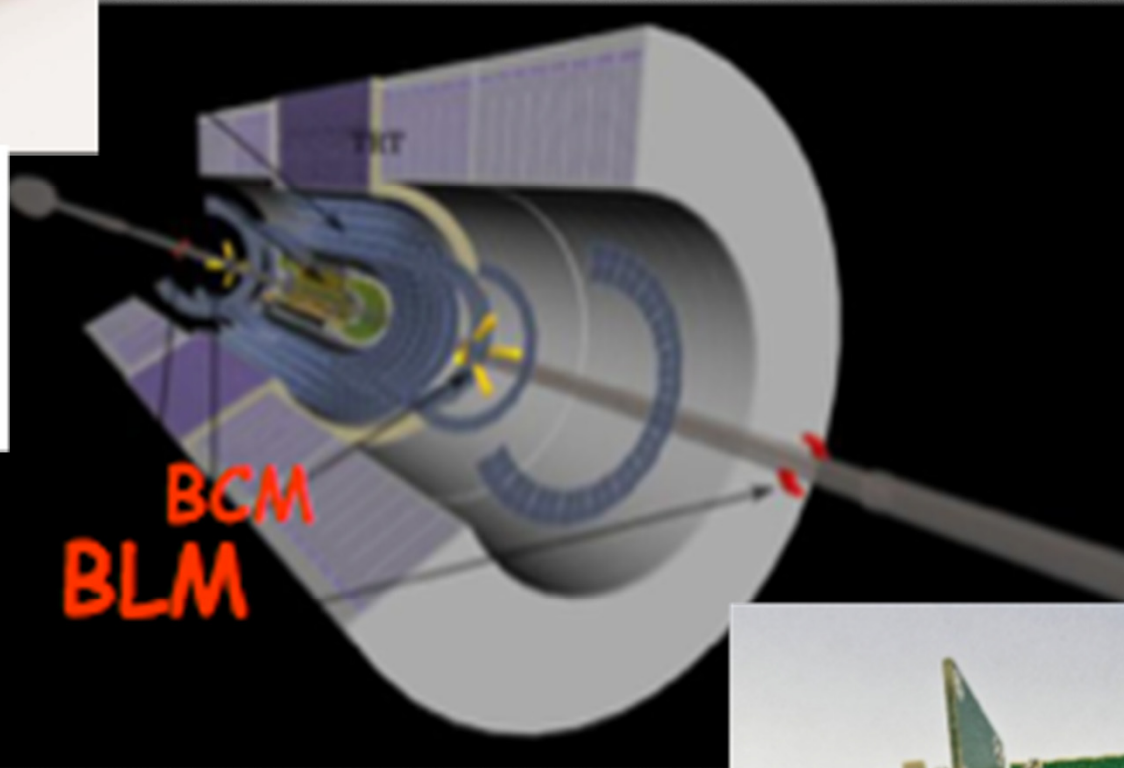
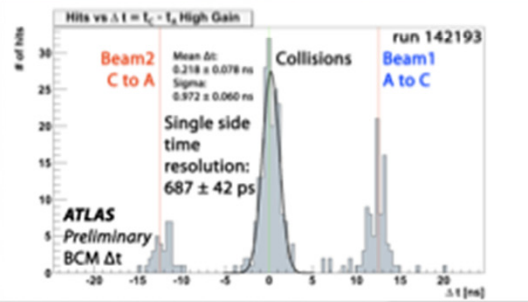
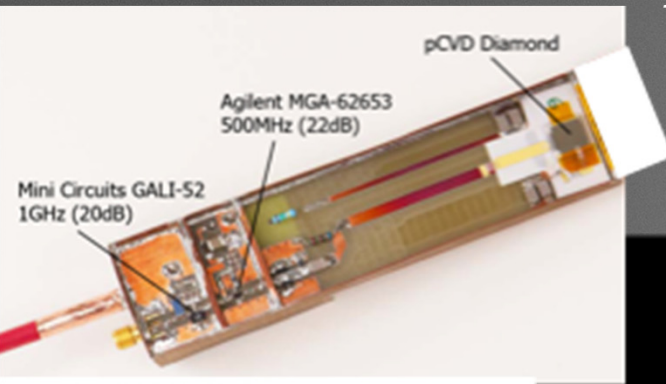
wafer to wafer
bonding



FE-I3 operated
through TSVs

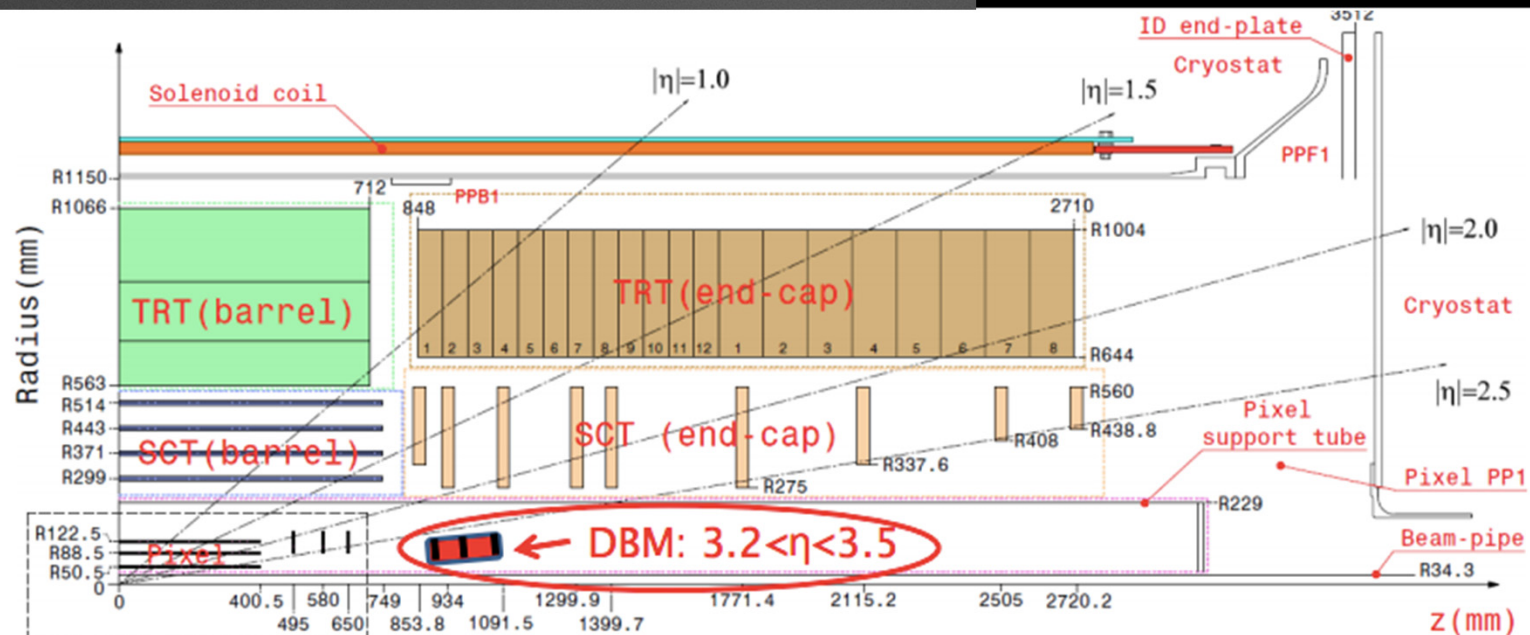
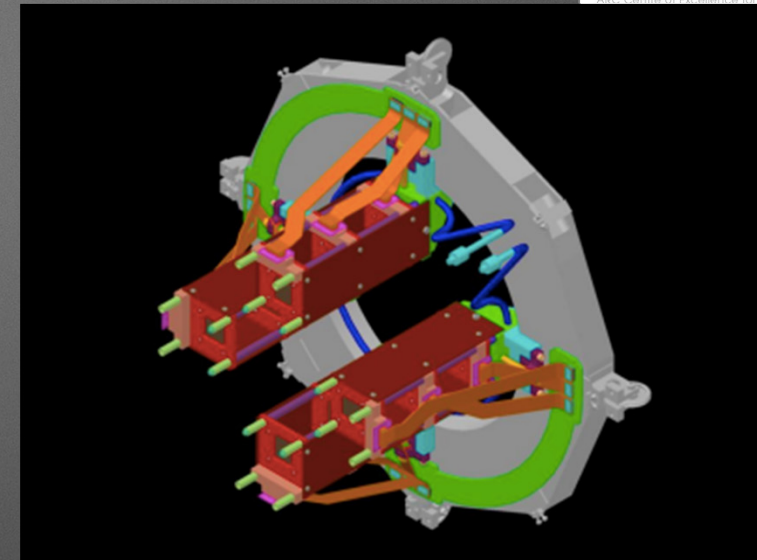
M. Barbero, T. Fritsch,
L. Gonella, F. Hügging et al.,
JINST 7 (2012) P08008

ATLAS Diamond Beam Condition Monitor and Beam Loss Monitor

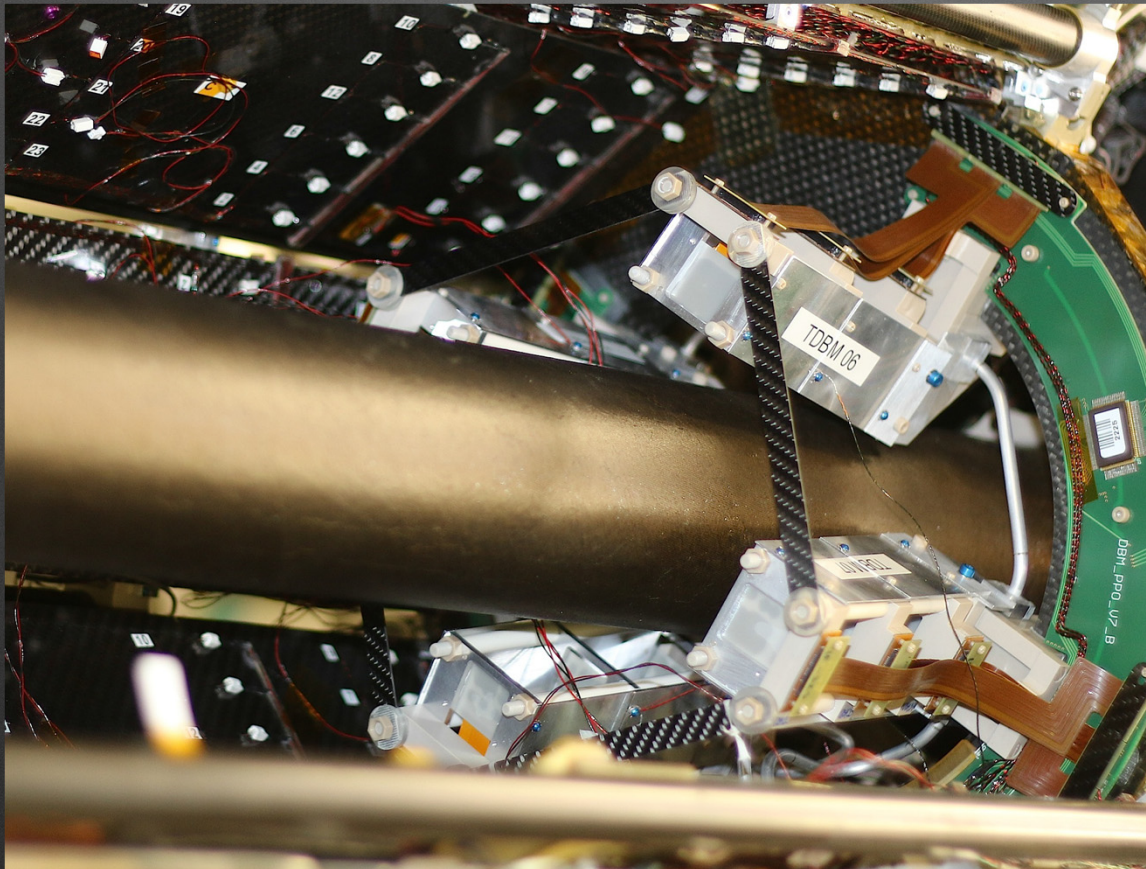


Diamond Beam Monitor

- Diamond offers advantages:
 - radiation hardness
 - fast signal response
 - simple processing



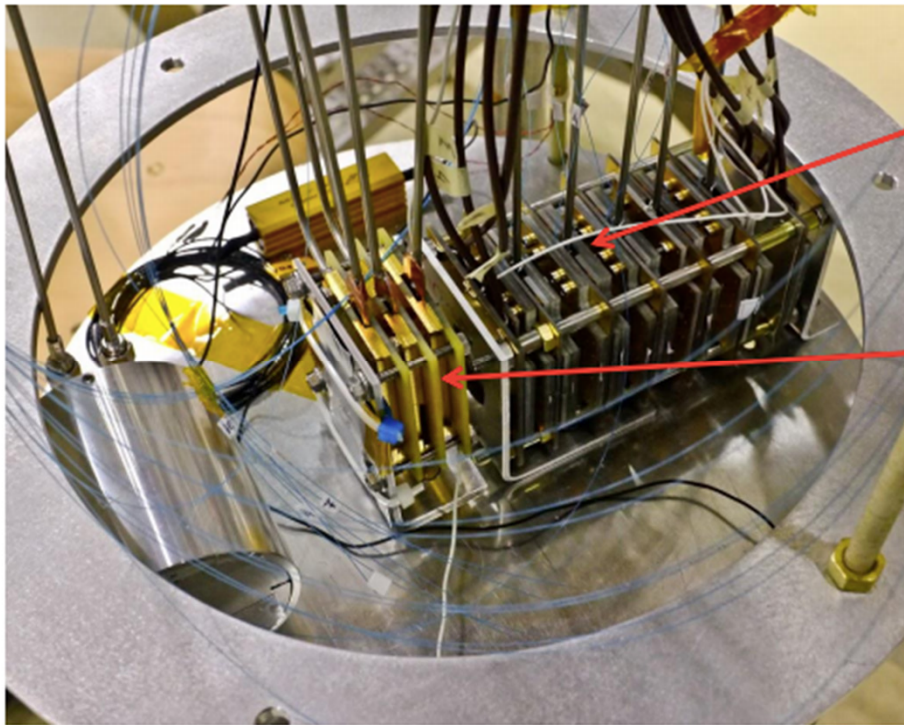
Diamond Detectors



Diamond Beam Monitor
IBL Pixel Layer

Si/Diamond as Cryogenic BLM

- Both seem capable of operation at LHe temperatures
- Suggest operation of BLM within magnet cryostat



6 p⁺-n-n⁺ silicon detectors of 4.5, 200, 500 and 10k Ω cm resistivity with Al metallisation (The thickness of the samples was of 300 μ m.)

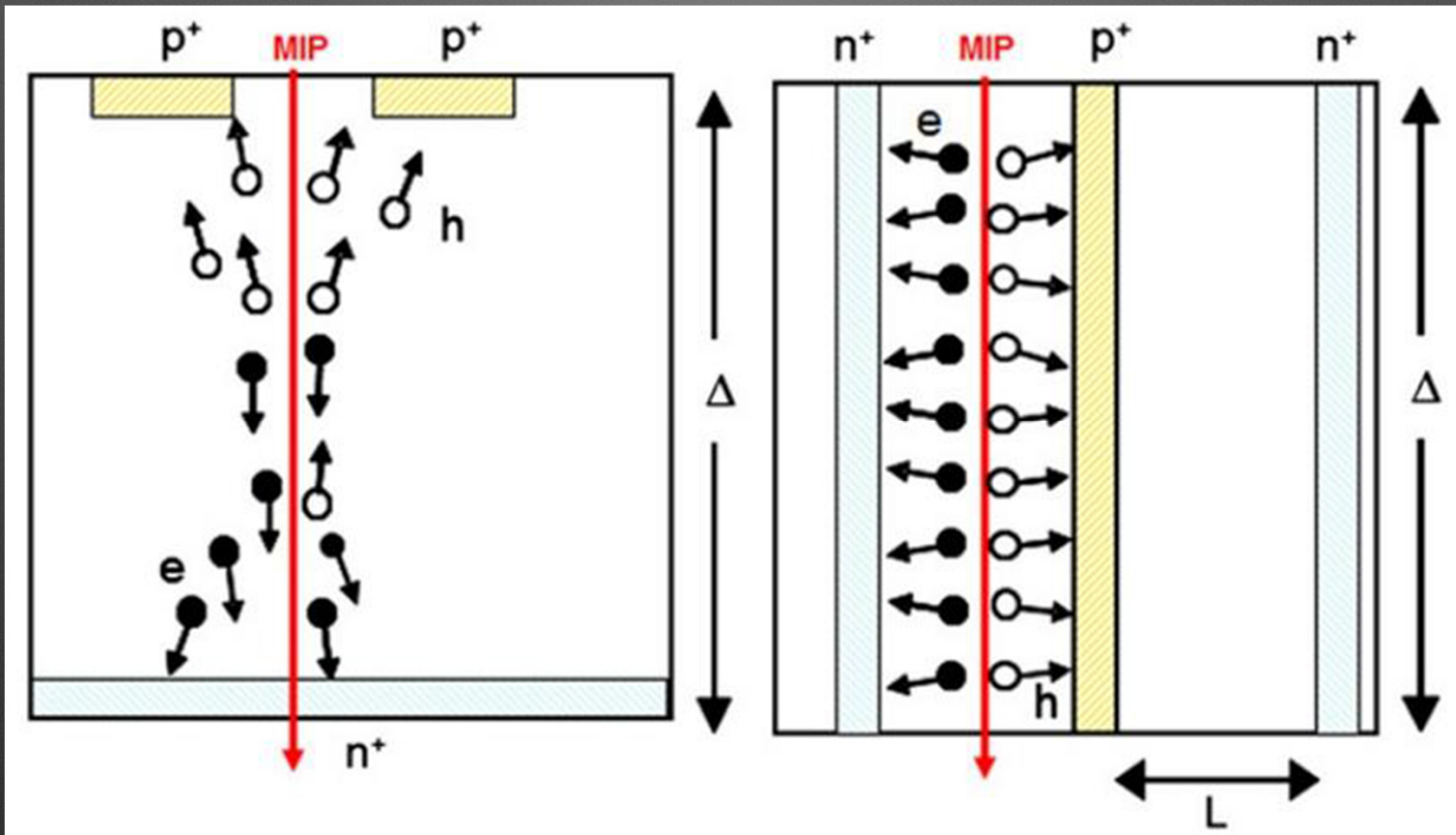
2 scCVD diamond detectors with a double layer metallisation of gold and titanium and a thickness of 500 μ m.

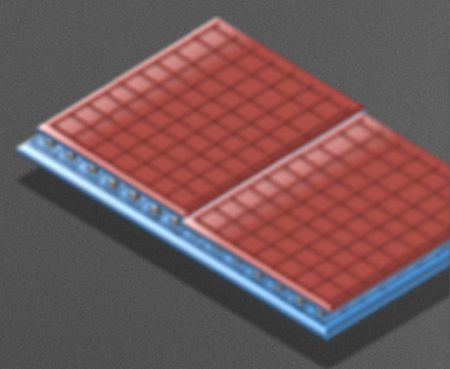
DC current generated by the beam was measured.

Kurfurst et al., NIM A782 (2015) 149

LHC

- Diamond detectors in beam monitoring.
- 3-D Detectors in ATLAS vertex detector



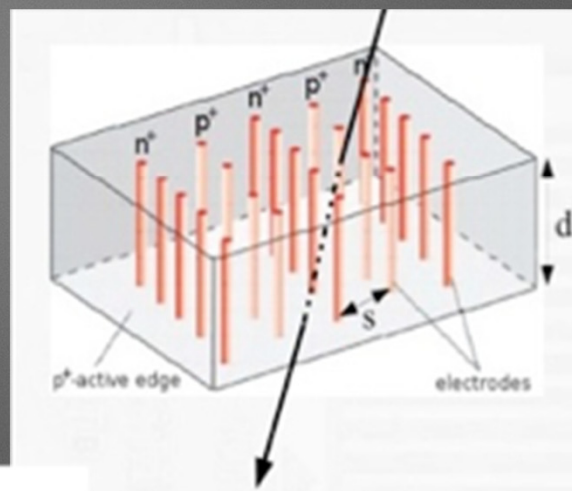


Planar Sensor

- "classic" sensor design
- oxygenated n-in-n
- 200 μ m thick
- Minimize inactive edge by shifting guard-ring under pixels (215 μ m)
- Radiation hardness for IBL to $5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$, tested up to $2.4 \times 10^{16} \text{ p}/\text{cm}^2$

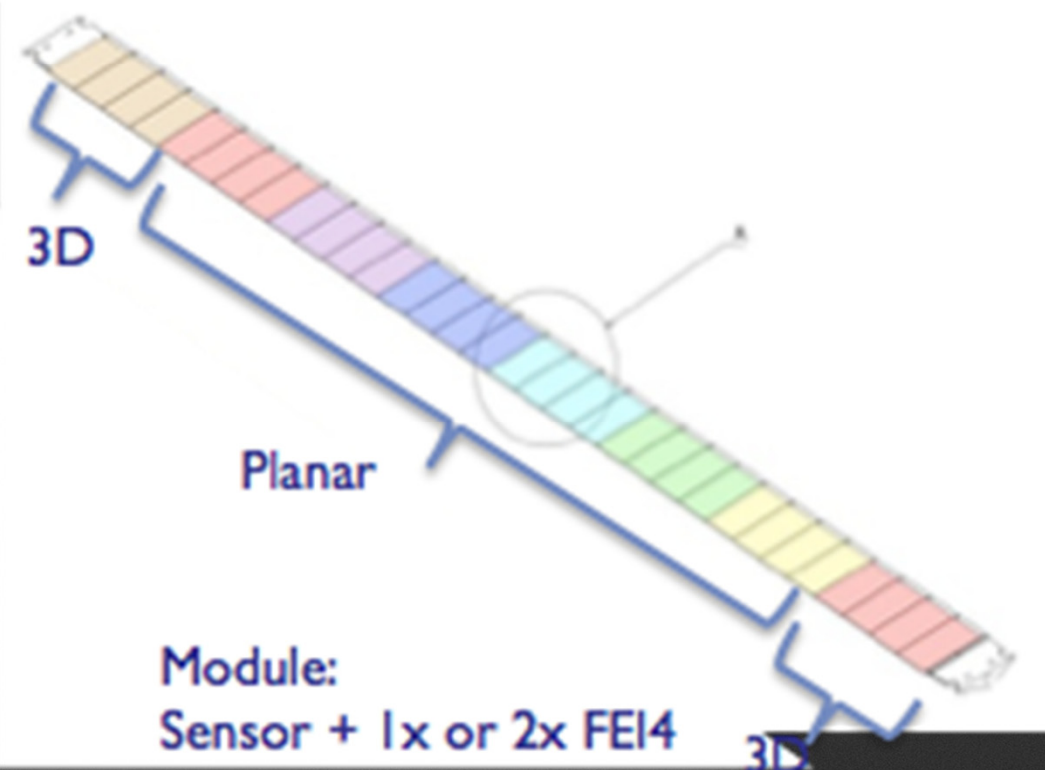
FE-I4 Pixel Chip (26880 channels)

19 x 20 mm² 130 nm CMOS process, based on an array of 80 by 336 pixels (each 50 x 250 μ m²)



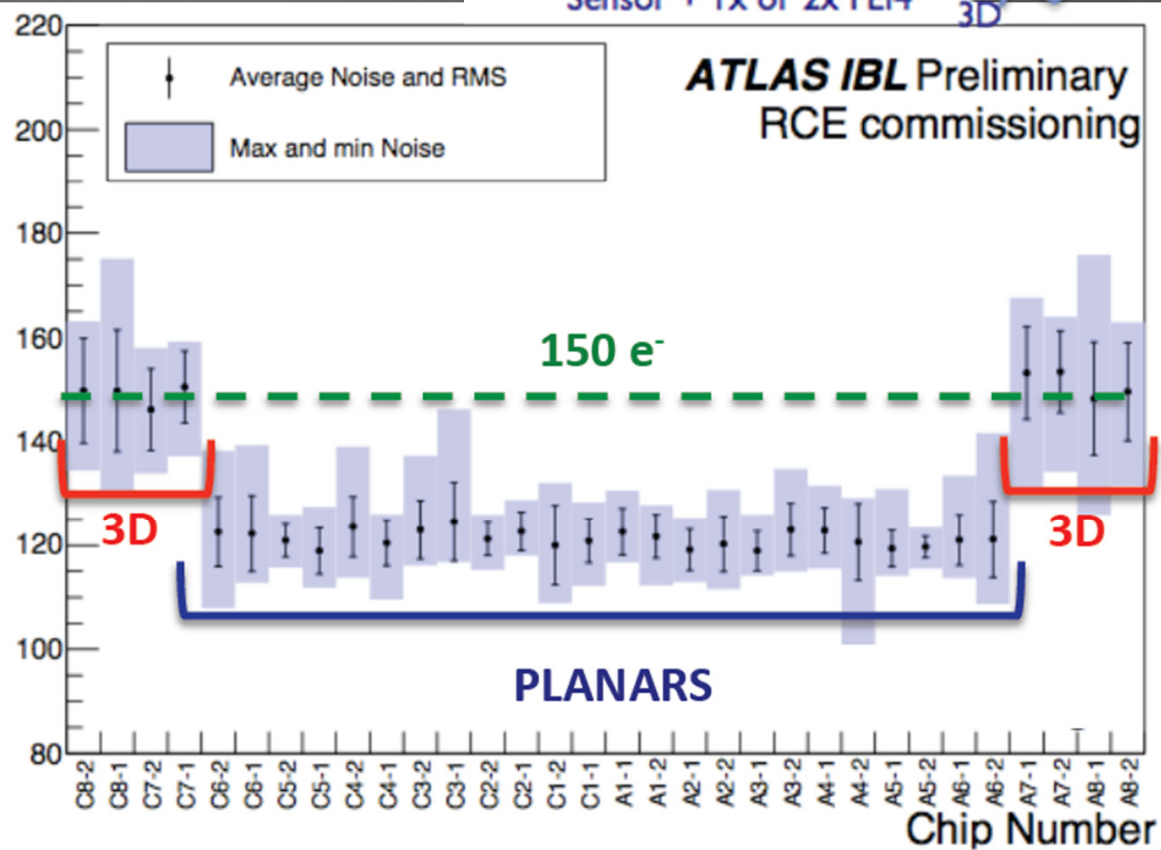
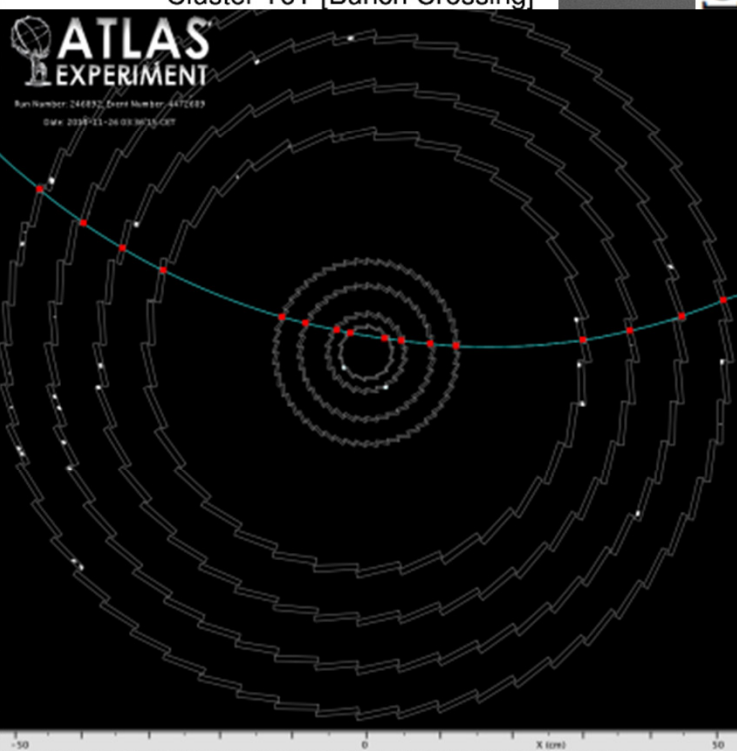
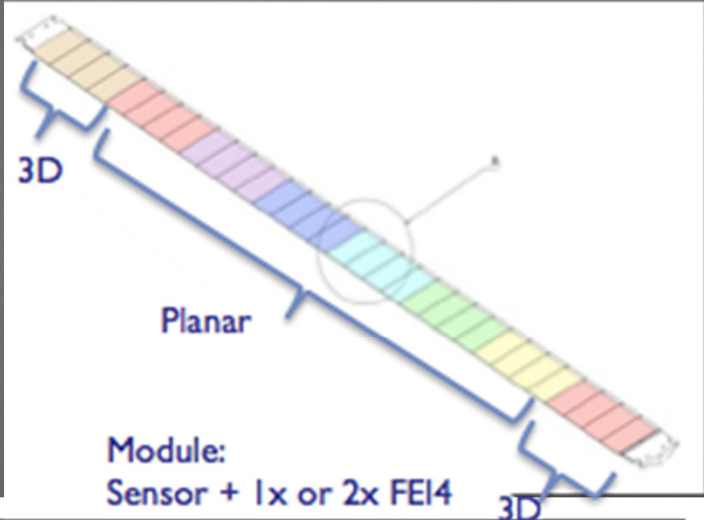
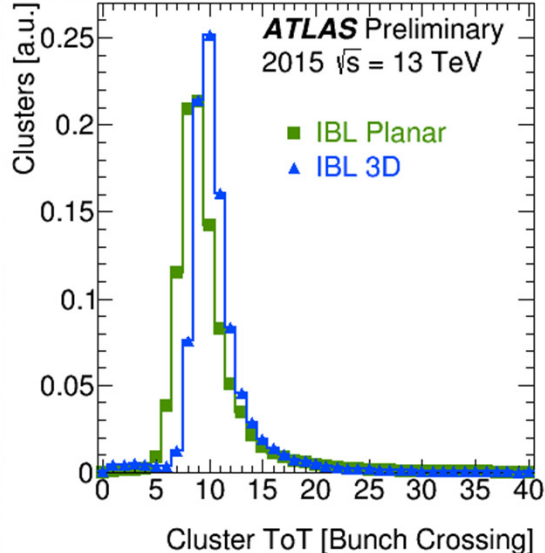
3D Sensor

- Both electrode types are processed inside the detector bulk
- Max. drift and depletion distance set by electrode spacing
- Reduced collection time and depletion voltage



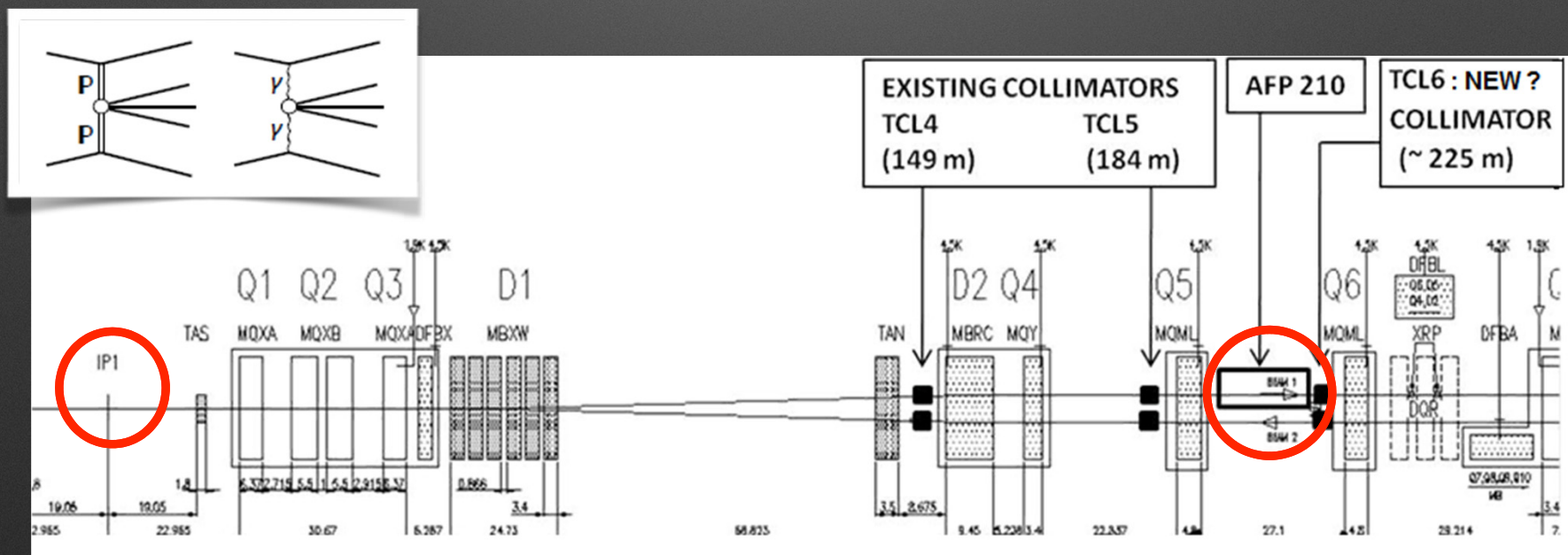
Module:

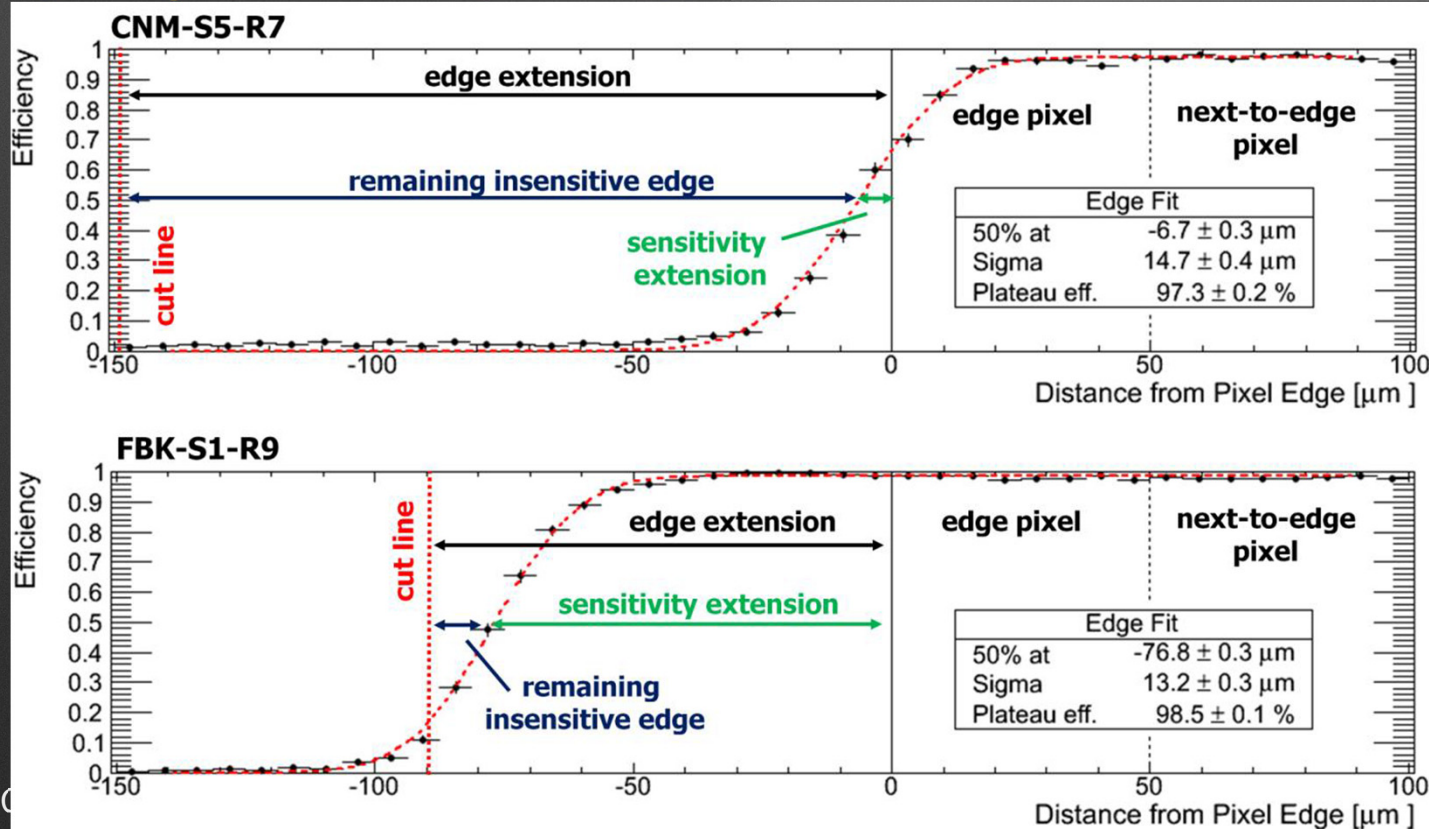
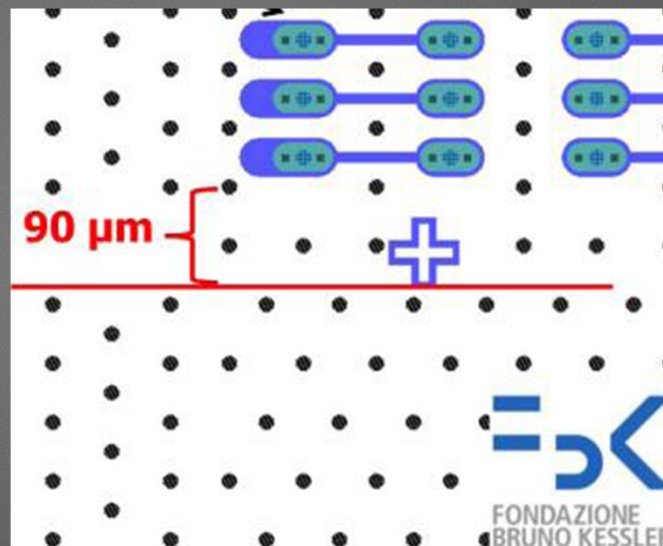
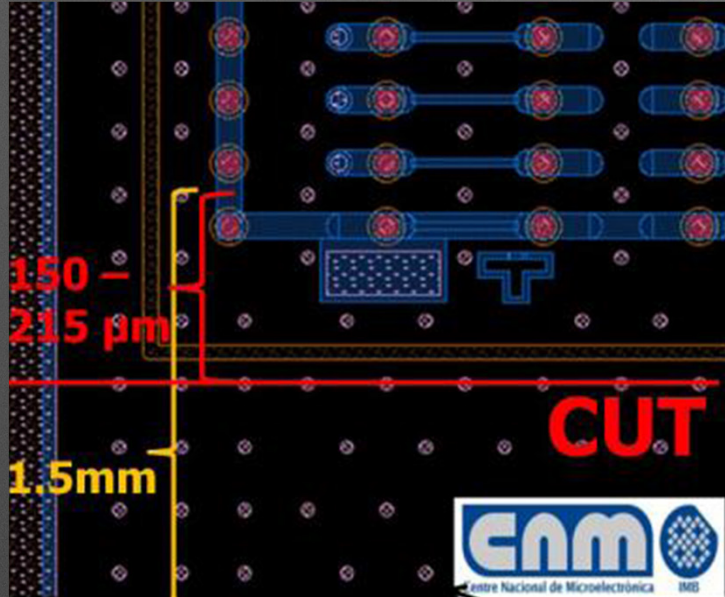
Sensor + 1x or 2x FEI4



“Forward” Physics Detectors

- Very small angle proton scattering:
 - Good spatial resolution ($\sim 10\mu\text{m}$)
 - Sensitivity close to edge.
 - Good radiation intolerance.
 - 3D detectors very promising.



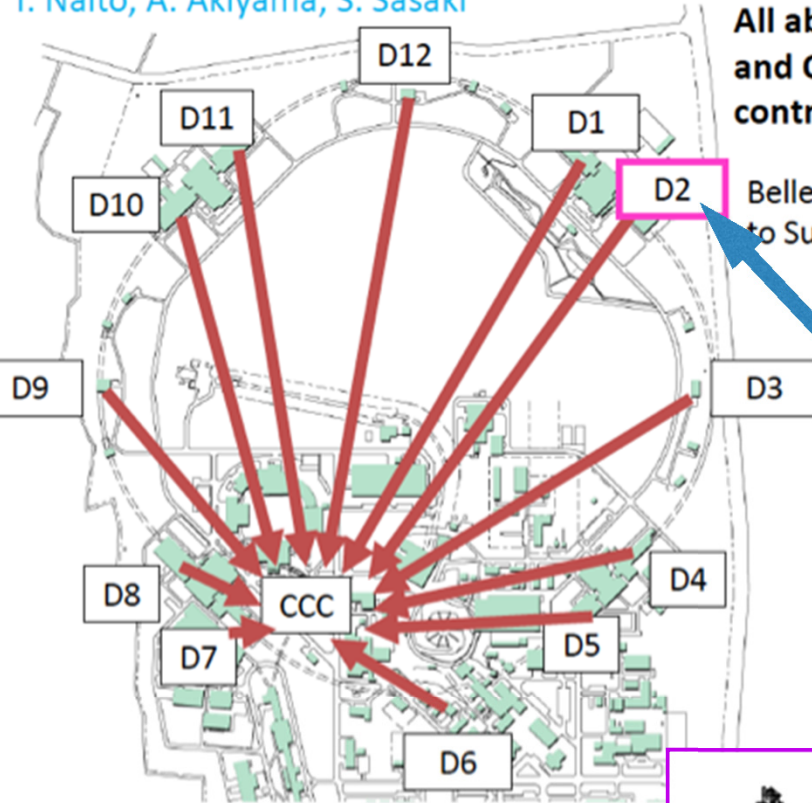


SuperKEKB - Diamond Beam Monitor

- Belle II Pixel and Strip Vertex Detector (VXD) Abort monitors

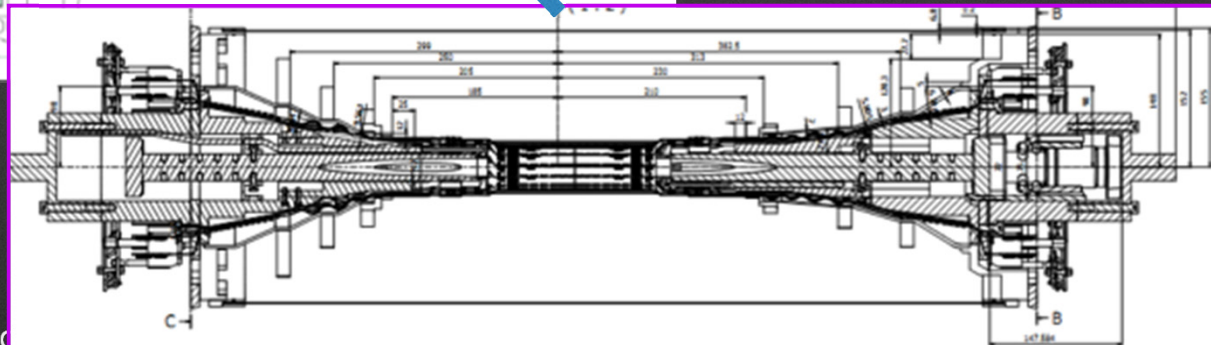
Abort trigger system for SuperKEKB

T. Naito, A. Akiyama, S. Sasaki

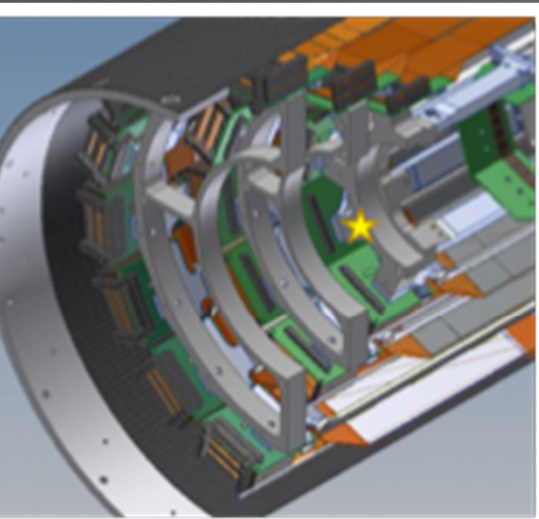


All abort trigger signal is gathered and ORed together, at the SuperKEKB control building.

BelleII Abort signal is sent to SuperKEKB via D2.

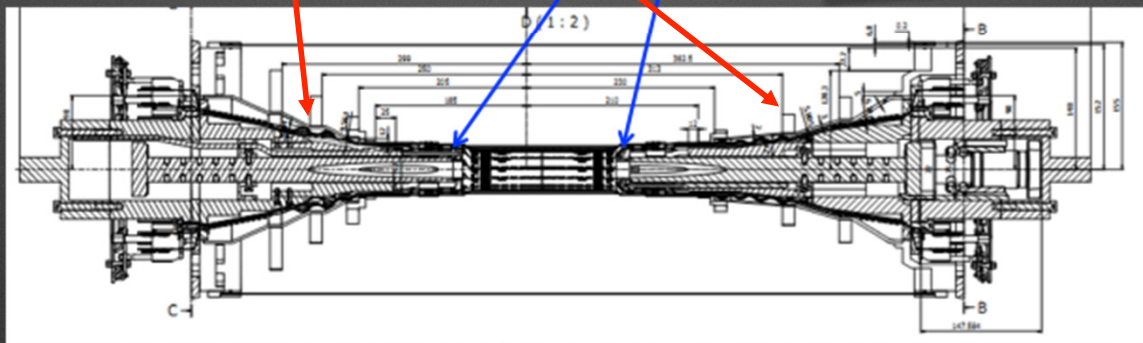
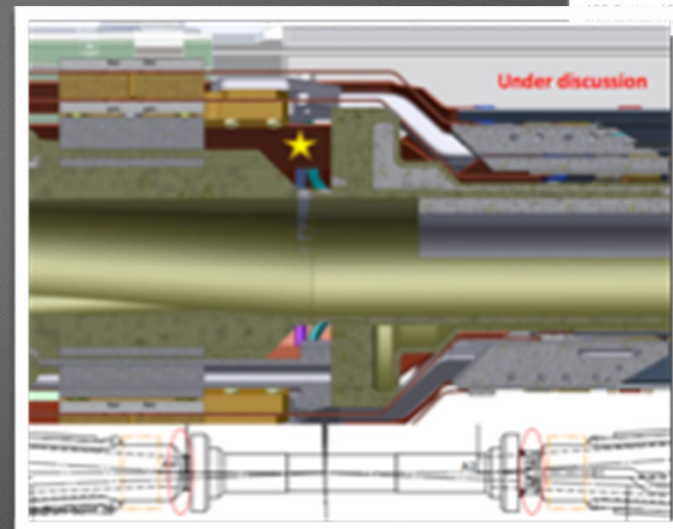


Belle II PXD Beam Abort

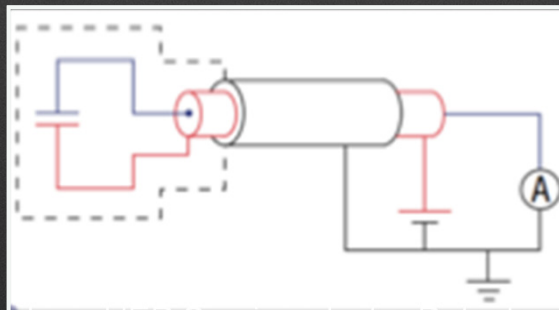


6 + 6 sensors
close to SVD L3
support rings

4 + 4 sensors
PXD-beam pipe

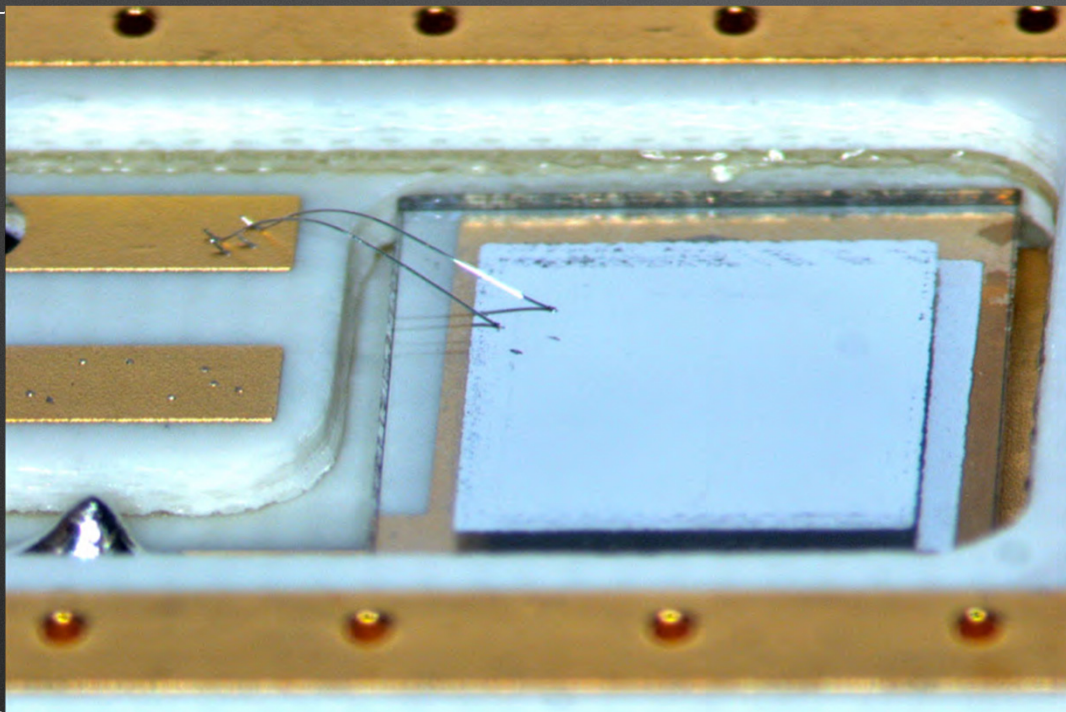


Shielded
diamond
sensors



3+15 m (3+40 m) cables
Voltage sources (150÷500 V)
picoAmmeters

- Based on experience from Belle, BaBar, CDF, LHC
- scCVD diamond sensors, measurement of currents:
 - typical pCVD sensor @ 500V:
 $1\text{ nA} = 7\text{ mrad/s} = 70\text{ }\mu\text{Gy/s}$
 - Noise a few pA, in current measurements



Outlook

- Silicon and Diamond detectors effective for both HEP detectors and Beam Monitoring / Beam Loss role.
- Pixel devices essential for high rate / high luminosity environments (SuperKEKB, LHC, HL-LHC)
- Si and Diamond capable of cryogenic operation
- HR-CMOS, HV-CMOS offer future technology for significant integration options.